## Size effects in metallic thin films

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The relaxation time derived with use of the thickness-dependent thin-film Thomas-Fermi impurity potential in the collision term of the Boltzmann transport equation is used to study the classical size effects in the Hall coefficient  $R_f$  and magnetoresistance  $M_f$  in metallic thin films. The theoretical prediction of  $R_f$  agrees well with experimental results. The dependence of  $M_f$  on thickness and magnetic field is also discussed.

A survey of the literature on the experimental and theoretical studies of metallic thin films<sup>1-13</sup> reveals that the transport properties, such as electrical resistivity  $\rho_f$ , magnetoresistance  $M_f$ , and the Hall coefficient  $R_f$ , show marked deviations from the bulk behavior, and the deviations become significant as the thickness becomes comparable with the mean free path of the electrons. In an earlier analysis<sup>10</sup> Ajoy, Devanathan, and Govindaraj (hereafter referred to as ADG) have shown the size-dependent behavior of  $\rho_f$  by using the energy, momentum, and thickness-dependent relaxation time  $\tau$ . In the present work, we have extended the ADG theory to study the other transport quantities, viz.,  $R_f$ and  $M_f$ , using  $\tau$ . The Hall coefficient  $R_f$  shows a size effect, and it is found that  $R_f$  is large for small thickness, and decreases with increasing thickness until it reaches the bulk value  $R_b$ . Magnetic field shows a very small size effect in  $R_f$ . At low magnetic field,  $R_f$  is slightly higher than its bulk value, and approaches the bulk value  $R_b$  at strong magnetic fields. Theoretical predictions of  $R_f$  agree with the experimental data on potassium films. The size effect in  $M_f$  is observed as a function of thickness and magnetic field.

The energy, momentum, and thickness-dependent relaxation time in ADG is given by

$$\tau = \frac{Kd}{4\pi\lambda^2 Nq_0^2 F} \left( \frac{1}{\lambda^4} + \frac{1}{[\lambda^2 + 4(2E - K^2)]^2} \right)^{-1} , \qquad (1)$$

where  $F = [(L_b/2)^2 + d^2]^{1/2} - d$ ,  $L_b$  is the bulk dimension, d is the thickness,  $\lambda = 6\pi n_0/E_F$ ,  $n_0$  is the electron concentration,  $E_F$  is the Fermi energy, N is the concentration of the impurity atoms,  $q_0$  is the charge of the impurity atom, K is the momentum, and E is the total energy of the electron. We use atomic units  $(e^2 = 1, \hbar = 1, m_e = 1)$  throughout this paper. Equation (1) serves as the basis for our analysis of the classical size effects in metallic thin films.

Expressions for the Hall coefficient  $R_f$  and the magnetoresistance  $M_f$  are derived for thin films using the relaxation time  $\tau$  by suitably modifying the bulk expressions.<sup>14</sup> Expressions for the x and y components of the current density,  $J_x$  and  $J_y$ , for the metallic thin film subjected to an electric field  $E_{0x}$ ,  $E_{0y}$ , in the plane of the film and transverse magnetic field **B** are given by

$$J_x = SE_{0x} + S^* E_{0y} \tag{2}$$

and

$$J_y = SE_{0y} - S^* E_{0x} \quad , \tag{3}$$

where

$$S = -\sum_{m} \int d^2 K \, \frac{\partial F_0}{\partial E} \frac{\tau}{1 + \tau^2 B^{*2}} K_j^2 D_{\mathbf{K},m} \tag{4}$$

and

$$S^* = -\sum_{m} \int d^2 K \; \frac{\partial F_0}{\partial E} \frac{\tau^2 B^*}{1 + \tau^2 B^{*2}} K_j^2 D_{\mathbf{K},m} \; . \tag{5}$$

 $\tau$  is the relaxation time given by Eq. (1),  $F_0 = \psi_{\mathbf{K},m}^*(\mathbf{r})\psi_{\mathbf{K},m}(\mathbf{r})f_0(E)$ ,  $\psi_{\mathbf{K},m}(\mathbf{r})$  is the wave function of the electron, and  $f_0(E)$  is the Fermi-Dirac distribution function given by

$$f_0(E) = \{ \exp[(E - E_F)/kT] + 1 \}^{-1} , \qquad (6)$$

where  $E = E_{K,m}$ ,  $E_F$  is the Fermi energy of the electron,  $K_j$  may be either the x or y component of K,  $D_{K,m}$  is the density of states at K,m, and  $B^* = B/c$ . Substituting Eq. (1) in Eqs. (4) and (5) and evaluating the integrals, we get

$$S = \frac{1}{8\pi^2 \lambda^2 N q_0^2 F} \sum_{m=1}^{m_{\text{max}}} A^{3/2} D^{-1} / H \quad , \tag{7}$$

and

$$S^* = \frac{B^* d}{32\pi^2 \lambda^4 N^2 q_0^4 F^2} \sum_{m=1}^{m_{\text{max}}} A^2 D^{-2} / H \quad , \tag{8}$$

where

$$A = [2E_F - (m\pi/d)^2] ,$$
  

$$D = \left(\frac{1}{\lambda^4} + \frac{1}{[\lambda^2 + (2m\pi/d)^2]^2}\right) ,$$
  

$$H = [1 + AG^2(\lambda^2 FD)^{-2}] \text{ with } G = B^* d/4\pi N .$$

Equations (2), (3), (7), and (8) are used in the calculation of  $R_f$  and  $M_f$ .

The Hall coefficient is defined by

$$R_f = \frac{E_{0y}}{BJ_x} \bigg|_{J_y = 0} \quad . \tag{9}$$

2628

32

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By combining Eqs. (2) and (3), we get

$$R_f = \frac{S^*}{B[S^2 + (S^*)^2]} \quad , \tag{10}$$

where S and  $S^*$  are given by Eqs. (7) and (8). The magnetoresistance is defined by

$$\rho(p \rightarrow 0) = \rho(p \rightarrow 0)$$

$$M_f = \frac{\rho(B \neq 0)}{\rho(B = 0)} \quad , \tag{11}$$

where

$$\rho_{(B\neq0)} = \frac{E_{0x}}{J_x} \bigg|_{J_y=0} \quad . \tag{11a}$$

Combining Eqs. (2) and (3), we get

$$\rho_{(B\neq0)} = \frac{S}{S^2 + (S^*)^2} \quad (11b)$$

Therefore

$$M_f = \frac{SU}{S^2 + (S^*)^2} - 1 \quad , \tag{12}$$

where U is the electrical conductivity  $\sigma_f$  and is the same as in Eq. (37) in ADG

$$\sigma_f = \frac{1}{4\pi^2 \lambda^2 N q_0^2 F} \frac{1}{2} \sum_{m=1}^{m_{\text{max}}} A^{3/2} D^{-1}$$

The quantities  $S^*$  and S are given by Eqs. (7) and (8).

The size effect in the Hall coefficient  $R_f$  is studied using Eq. (10). Figure 1 shows the thickness-dependent behavior of the Hall coefficient  $R_f$  for potassium thin films. The value of  $R_f$  is calculated in the presence of magnetic field  $B = 10^3$  G. Figure 1 clearly explains that the Hall coefficient is large for small thickness, and decreases with increasing thickness until it reaches the bulk value  $R_b$  at large thickness. The values of  $R_f$  are found to be in good agree-



FIG. 1. The Hall coefficient as a function of thickness for potassium thin film. Experimental data on potassium thin film at 90 K (Ref. 15).

ment with the experimental results.<sup>15</sup> The value of  $R_f$  is also calculated for Cu and Ag thin films, and size effects in Cu and Ag are smaller than those for K at a given thickness. The field effect on  $R_f$  is studied, and it is found that for d = 100 a.u.,  $R_f$  remains almost constant up to  $10^5$  G, and for d = 1000 a.u., a small decrease in  $R_f$  is observed at about  $3 \times 10^3$  G and is just 1% at  $10^5$  G. The same effect is also observed for other metallic films. However, the variation of  $R_f$  with magnetic field is very small.

Equation (12) is used to study the dependence of magnetoresistance  $M_f$  upon thickness d and magnetic field B. The value of  $M_f$  is calculated for various values of d in the pres-



FIG. 2. Magnetoresistance as a function of thickness for copper thin films. Fur curve A,  $B = 10^3$  G, for curve B,  $B = 10^2$  G.



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ence of magnetic field  $(B = 10^2 \text{ and } 10^3 \text{ G}, \text{ respectively})$ , and the dependence of  $\log M_f$  on *d* is shown in Fig. 2. At small thickness, though, the value of  $M_f$  is very small, and the variation of  $M_f$  is large. At large thickness, the value of  $M_f$  is large, but its variation is small. The value of  $M_f$  approaches a constant value when the thickness reaches the bulk value. The value of  $M_f$  is calculated for d = 50, 100, and 1000 a.u. in the presence of different values of magnetic field and the variation of  $\log M_f$  with  $\log B$  is plotted in Fig. 3. At low magnetic field,  $M_f$  is very small, but its variation with field is large. However at strong field, the value of  $M_f$  is large, and its variation with field is small. The value of  $M_f$  reaches a constant value when the field attains  $10^7 \text{ G}$ .

The present study on the Hall coefficient and magnetoresistance explains the existence of the size effect in metallic thin films as explained in other theories.<sup>1,2,5</sup> However, the present model does not include the specular parame-

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ter p for surface reflection, to explain the thickness dependence of  $R_f$  and  $M_f$ . The value of  $R_f$  is found to be larger than the bulk value, and the thickness dependence is observed down to  $10^4$  a.u. The thickness and magnetic field dependence features of  $M_f$  in the present model are similar to what has been observed in other works.<sup>2,5,7</sup>

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